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APPLICATION NO. FILING		ILING DATE	DATE FIRST NAMED INVENTOR		CONFIRMATION NO.	
10/615,806	10/615,806 07/10/2003		Hiroyuki Sonoda	8019-1031	1907	
466	7590	08/08/2005		EXAMINER		
YOUNG &			NGUYEN, TUAN H			
745 SOUTI 2ND FLOC		REET	ART UNIT T	PAPER NUMBER		
ARLINGTO		22202	2813			
				DATE MAILED: 08/08/2009	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applicat	ion No.	Applicant(s)						
Office Action Summary		10/615,8	06	SONODA ET AL.	(m)					
		Examine	r	Art Unit						
		Tuan H. I		2813						
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply										
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).										
Status										
1)⊠ R€	esponsive to communication(s) filed	l on 01 June 2005								
•=										
3)□ Si	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.									
Disposition	of Claims	,								
4a 5)□ Cl 6)⊠ Cl 7)□ Cl	4) ☐ Claim(s) 1-13 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-13 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or election requirement.									
Application	Papers									
9)∐ Th	e specification is objected to by the	Examiner.								
10) <u> </u>	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.									
Ap	plicant may not request that any object	tion to the drawing(s)	be held in abeyance	e. See 37 CFR 1.85(a).						
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.									
Priority und	ler 35 U.S.C. § 119		•							
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 										
Attachment(s)			_							
	f References Cited (PTO-892) f Draftsperson's Patent Drawing Review (PT	TO 048)		mmary (PTO-413) /Mail Date						
3) 🔲 Informat	r Draπsperson's Patent Drawing Review (P1 ion Disclosure Statement(s) (PTO-1449 or Fo(s)/Mail Date			ormal Patent Application (PTO-15	52)					

Application/Control Number: 10/615,806

Art Unit: 2813

DETAILED ACTION

Allowable Subject Matter

The indicated allowability of claim 2 is withdrawn in view of the newly discovered reference(s) to Kezuka et al.. Rejections based on the newly cited reference(s) follow.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

Claims 1-6, 8, 10-13 are rejected under 35 U.S.C. 102(e) as being anticipated by Kezuka et al..

See Kezuka et al., particular Test Example 5 on col. 14, last two paragraphs which discloses the claimed method for removing polymer adhered to a sidewall of an etched metal layer (col. 10, lines 54-59) formed on a substrate including dissolving the polymer

by providing chemicals onto a surface of the substrate (ashing with an oxygen gas and immersing in the chemical composition, col. 14, lines 60-64); rinsing the chemicals out of the substrate by providing pure water onto a surface of the substrate (col. 14, lines 64-66).

With respect to claims 2, 3, 4, the process of rinsing the wafer, after immersing in the composition to remove the polymer from the sidewall, is performed in an open air that is an oxidation atmosphere.

With respect to claims 5, 6, see col. 10, lines 35-39 for the step of cleaning by supplying the composition onto the article while rotating it. This process is carry out in an open air or in oxidation atmosphere.

With respect to claim 8, the step (a) is carried out in the open air and is considered as an oxidation atmosphere.

With respect to claims 10-12, see col. 10, lines 49-50; col. 14, lines 55-57.

With respect to claim 13, see col. 6, line 25.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 7, 9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kezuka et al..

Kezuka et al., particular Test Example 5 on col. 14, last two paragraphs which discloses substantially the claimed method for removing polymer adhered to a sidewall of an etched metal layer formed on a substrate as explained above, except the step of drying, and repeatedly carried out step (a) and (b); however, it would have been obvious to one having ordinary skill in the art at the time the invention was made to have recognized that the substrate is inherently dried for a subsequent step of forming metal contact, and it would also obvious to those skilled in the art to repeatedly carried out steps (a) and (b) until the polymer residue is removed and the substrate is cleaned.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Zhou et al., Wu et al., '482, Wu et al., '033, Iwamoto et al. teach the step of removing polymer residue.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tuan H. Nguyen whose telephone number is 571-272-1694. The examiner can normally be reached on 9AM-5:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Tuan H. Nguyen
Primary Examiner
Art Unit 2813

TN